





The PPD ablation technique allows to fabricate thin films to CdTe with excellent composition and morphology (see inset). The composition transfer from the target to the substrate enables the fabrication of CdTe in a safe environment. The low roughness of the films (~ 100nm r.m.s.) allows to generate well defined interfaces. The proprietary fabrication process has been transferred to Siena Solar Nanotech (2SN), a spin-off of Organic Spintronics.

- Low temperature (up to RT)
- Low roughness
- High deposition rate
- Environmentally friendly fabrication technology

Eg (eV)	Roughness nm (r.m.s.)	Typical deposition rate at 20 Hz (nm/min)
1.57	100	100



Fig. 1 SEM image of CdTe made by PPT

(by courtesy of 2SN)